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Atty. Dkt. No. APPM/004150.D1(Y2)/ETCH/DRIE/MDAO

IN THE CLAIMS:

Please amend the claims as follows, adding new claims 40-46:

1.-10 (Cancelled)

11. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls, a substrate support, and a bottom of a processing chamber, comprising:

a liner adapted to be removably disposed in the processing region and having a base for substantially covering the bottom of the processing chamber, wherein the liner further comprises:

an outer cylindrical wall contacting an outer edge of the base for extending into the processing region along the sidewalls, the outer cylindrical wall having a first protrusion spaced above the base; and

an inner cylindrical wall connected to an inner edge of the base for extending into the processing region along the substrate support, the inner cylindrical wall having a second protrusion located opposite the first protrusion; and

a magnet located in the second protrusion on the inner cylindrical wall of the liner.

12. (Currently Amended) The apparatus of claim 11, wherein a circular passage is formed at least partially in the base, at least a portion of the circular passage is defined between the base and the bottom of the chamber, and the circular passage is adapted to fluidly isolate a heat transfer fluid flowing through the base.

13. (Currently Amended) The apparatus of claim 11, wherein the liner has further comprises:

a circular passage formed at least partially in the base; and

a first boss and a second boss interfacing with apertures formed in the bottom of the processing chamber and projecting from the base, the first boss comprising a hole

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in fluid communication with the circular passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the circular passage at an outlet of the passage.

14. (Currently Amended) The apparatus of claim 12, wherein the circular passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.

15. (Currently Amended) The apparatus of claim 11, wherein the inner liner comprises a cylindrical wall is sized to cover the substrate support with minimal clearance.

16. (Currently Amended) The apparatus of claim ~~45~~ 13, wherein the circular passage is formed at least partially in the bottom of the processing chamber cylindrical wall.

17. (Currently Amended) The apparatus of claim ~~45~~ 13, wherein the first boss and the second boss aligns the base relative to the bottom of the processing chamber cylindrical wall comprises a lip extending into the process volume.

18. (Currently Amended) The apparatus of claim ~~45~~ 11, wherein the cylindrical wall comprises a magnet comprises samarium disposed therein.

19. (Currently Amended) The apparatus of claim ~~45~~ 13, wherein the first boss and the second boss cylindrical wall comprises:

- a quick-connect coupling
- a lip extending to the process volume; and
- a magnet disposed therein.

20. (Currently Amended) The apparatus of claim ~~45~~ 11, further comprising:
a second liner coupled to the outer cylindrical wall along wherein the cylindrical wall is configured to line the sidewalls of the chamber and extending to a lid assembly.

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21. (Currently Amended) The apparatus of claim ~~15~~ 20, wherein the second liner comprises an outwardly extending flange ~~cylindrical wall is configured to line a substrate support disposed in the process volume of the chamber.~~
22. (Previously Presented) The apparatus of claim 11, wherein the liner further comprises:
- a passage formed at least partially in the base and adapted to fluidly isolate a heat transfer fluid flowing therethrough from the processing region, the passage being fluidly isolated from the processing region; and
 - a bottom coupled between the outer cylindrical wall and the inner cylindrical wall.
23. (Original) The apparatus of claim 11, wherein the liner is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
24. (Original) The apparatus of claim 11, wherein the liner comprises:
- a textured interior surface adapted to be exposed to the interior volume.
25. (Previously Presented) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:
- an annular base having a perimeter, for substantially covering the bottom of the processing chamber;
 - a first cylindrical wall extending from the perimeter of the base;
 - a substantially annular passage formed at least partially in the base; and
 - a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage, wherein the first boss and the second boss are configured to extend through the processing chamber.

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26. (Original) The apparatus of claim 25, wherein the passage is adapted to isolate a heat transfer fluid flowing therethrough from the process volume.
27. (Cancelled)
28. (Original) The apparatus of claim 25, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
29. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a lip extending radially inwards in a spaced-apart relation to the base.
30. (Previously Presented) The apparatus of claim 25 further comprising a second cylindrical wall coupled to an inner portion of the base.
31. (Original) The apparatus of claim 25, wherein the base and first cylindrical wall are comprised of a material selected from the group of aluminum, ceramic and stainless steel.
32. (Original) The apparatus of claim 25, wherein the first cylindrical wall comprises a textured inner surface.
33. (Currently Amended) A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:
an annular base for substantially covering the bottom of the chamber;
a first cylindrical wall coupled to an outer portion of the base for extending into the processing region along the sidewalls of the chamber;
a second cylindrical wall coupled to an inner portion of the base for extending into the processing region along a substrate support positioned therein;
a ridge extending from the first cylindrical wall toward the second cylindrical wall in a spaced-apart relation to the base

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~~a second cylindrical wall coupled to an inner portion of the base for extending into the processing region along a substrate support positioned therein; and~~

a substantially annular passage formed at least partially in the base, the passage being fluidly isolated from the processing region.

34. (Cancelled)

35. (Previously Presented) The apparatus of claim 33, wherein a passage is at least partially disposed in at least one of the first or second cylindrical walls.

36. (Currently Amended) A thermally controlled apparatus for lining a processing region ~~at least partially defined by walls of a processing chamber~~, comprising:

a processing chamber having walls surrounding the processing region;

a cylindrical liner section adapted to line at least a portion of the walls of the processing chamber;

a center section coupled to one end of the cylindrical section, the cylindrical section and the center section being exposed to the processing region and comprising a single piece structure, for substantially covering an upper surface of the chamber; and

a substantially annular passage at least partially formed in the center section, the passage being fluidly isolated from the processing region, wherein the substantially annular passage is coupled to a boss that extends through an aperture formed in the processing chamber.

37. (Currently Amended) A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:

a removable center member for substantially covering an upper surface of the chamber, the center member having a first side adapted to be exposed to the processing region;

a cylindrical wall extending from the first side of the center member and adapted to line at least a portion of the walls of the processing chamber; and

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a substantially annular passage at least partially formed in the center member, the passage adapted to isolate a heat transfer fluid flowing therethrough from the processing volume.

38. (Original) The apparatus of claim 37 further comprising a lid disposed proximate the center member and defining a plenum at least partially therewith.
39. (Original) The apparatus of claim 38, wherein the center member further comprises a plurality of nozzles disposed in the center member providing fluid access between the plenum and a side of the center member opposite the lid.
40. (New) The apparatus of claim 25, wherein the first boss and the second boss extend through apertures formed in the processing chamber to align the annular base.
41. (New) The apparatus of claim 33, wherein the bottom of the processing chamber comprises an aperture sized to receive a portion of the annular base.
42. (New) The apparatus of claim 41, wherein the aperture is sized to receive a boss coupled to the substantially annular passage.
43. (New) The apparatus of claim 41, wherein the first cylindrical wall and the annular base compress an o-ring positioned between the aperture and the annular base when a lid assembly is coupled to a top of the processing chamber.
44. (New) The apparatus of claim 33, wherein the bottom of the processing chamber further comprises:
an aperture to provide fluid to the substantially annular passage; and
an o-ring to provide a seal between the annular base and the substantially annular passage.

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45. (New) The apparatus of claim 36, wherein the boss and the aperture align the center section relative to the processing chamber.

46. (New) The apparatus of claim 45, wherein the aperture includes an o-ring that is compressed to form a seal between the processing chamber and the center section.